

Process for void-free metallic diffraction gratings for enhanced X- ray interferometry imaging Patent Application 17/972,816

Description

Problem:

Improvement is needed in X-ray phase contrast imaging systems for better imaging outcomes for soft tissues without the need for radioactive contrast agents.

Invention:

A process for creating a metallic diffraction grating with recessed features that is optimized for metallic void-free filling by electro-deposition.

CONTACT

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Also see patents 11,579,344 and 10,889,908

Benefits

Commercial Applications:

- X-ray interferometry
- X-ray phase contrast imaging
- X-ray wave-front-sensing
- Optics characterization
- Optics alignment
- Focus characterization at X-ray free-electron lasers (XFELs)
- Biomedicine
- Materials Science
- Security

Competitive Advantages:

- Minimal deposits on the field
- Reduction in post-deposition processing time.
- Void-free filled recessed feature with
- highly uniform filling profiles.

